

10763175_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10763175 on May 27, 2004

Original Classifications

15	250/492.22
7	250/492.2
5	355/53
4	430/5
3	250/398
2	430/22

Cross-Reference Classifications

13	250/398
6	250/492.2
5	250/492.22
5	250/492.23
5	430/296
4	250/396R
4	430/942
3	250/492.3
3	313/470
3	355/67
3	430/30
2	313/403
2	355/77
2	430/323
2	430/328
2	430/394
2	430/396
2	430/494
2	445/47

Combined Classifications

20	250/492.22
16	250/398
13	250/492.2
6	250/492.23
5	355/53
5	430/296
5	430/5
4	250/396R
4	430/30
4	430/942
3	250/492.3
3	313/470
3	355/67
3	430/22

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3 430/394
3 430/396
2 313/403
2 355/77
2 430/23
2 430/24
2 430/26
2 430/323
2 430/328
2 430/494
2 445/47

10763175_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

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20	250/492.22	(15 OR, 5 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
	250/492.22	..Pattern control
16	250/398	(3 OR, 13 XR)
	Class 250 :	RADIANT ENERGY
	250/396R	WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
	250/398	.With target means
13	250/492.2	(7 OR, 6 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
6	250/492.23	(1 OR, 5 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
	250/492.23	..Variable beam
5	355/53	(5 OR, 0 XR)
	Class 355 :	PHOTOCOPYING
	355/18	PROJECTION PRINTING AND COPYING CAMERAS
	355/53	.Step and repeat
5	430/296	(0 OR, 5 XR)
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
	430/269	IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
	430/296	.Electron beam imaging
5	430/5	(4 OR, 1 XR)
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
	430/4	RADIATION MODIFYING PRODUCT OR PROCESS OF MAKING

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430/5 .Radiation mask

4 250/396R (0 OR, 4 XR)

Class 250 : RADIANT ENERGY

250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING

4 430/30 (1 OR, 3 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
OR MEASUREMENT

4 430/942 (0 OR, 4 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/942 ELECTRON BEAM

3 250/492.3 (0 OR, 3 XR)

Class 250 : RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.3 .Ion or electron beam irradiation

3 313/470 (0 OR, 3 XR)

Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES

313/364 CATHODE RAY TUBE

313/461 .Screen

313/470 ..Mosaic

3 355/67 (0 OR, 3 XR)

Class 355 : PHOTOCOPYING

355/18 PROJECTION PRINTING AND COPYING CAMERAS

355/67 .Illumination systems or details

3 430/22 (2 OR, 1 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/22 REGISTRATION OR LAYOUT PROCESS OTHER THAN COLO

R

PROOFING

3 430/394 (1 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/394 PLURAL EXPOSURE STEPS

3 430/396 (1 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,

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COMPOSITION, OR PRODUCT THEREOF

430/396 EFFECTING FRONTAL RADIATION MODIFICATION DURING, ETC.

2 313/403 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/364 CATHODE RAY TUBE
313/402 .Shadow mask, support or shield
313/403 ..Non-circular aperture

2 355/77 (0 OR, 2 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/77 .Methods

2 430/23 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF

2 430/24 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF
430/24 .Using specific control or specific
modification of exposure, i.e., by manipulation of
radiation source or exposure through elements other than
shadow mask

2 430/26 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/23 PRODUCING CATHODE-RAY TUBE OR ELEMENT THEREOF
430/26 .With faceplate of phosphoric stripes

2 430/323 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR

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PRINTING SURFACE - PROCESS, COMPOSITION,

OR PRODUCT

430/322 .Forming nonplanar surface
430/323 ..Including etching substrate

2 430/328 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR

PRINTING SURFACE - PROCESS, COMPOSITION, O

R PRODUCT

430/328 .Post imaging radiant energy exposure

2 430/494 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/494 INCLUDING EXPOSURE STEP OR SPECIFIED
PRE-EXPOSURE STEP PERFECTING EXPOSURE

2 445/47 (0 OR, 2 XR)

Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR
DEVICE MANUFACTURING

445/1 PROCESS

445/46 .Electrode making

445/47 ..Multi-apertured panel making, e.g., CRT mask